

PTO/SB/08A (10-01)

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|   |   |    | Application Number       | 10/666,671             |         |
| <b>INFORMATION DISCLOSURE<br/>STATEMENT BY APPLICANT</b><br><br>(use as many sheets as necessary) |   |    | Filing Date              | 9/17/03                |         |
|   |   |    | First Named Inventor     | Shi                    |         |
|   |   |    | Art Unit                 | 1765                   |         |
|   |   |    | Examiner Name            | Not Yet Assigned       |         |
| Sheet   | 1 | of | 10                       | Attorney Docket Number | P118-US |

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|-----------------------------------|--------------------------|--|--------------------------------|--|---|
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| Sheet 2 of 10   | Attorney Docket Number | P118-US                  |                  |

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|   |   |    |    | Examiner Name            | Not Yet Assigned |
|   |   |    |    | Attorney Docket Number   | P118-US          |
| Sheet   | 3 | of | 10 |                          |                  |

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| LV                                | CE                       | JP-1997/09251981-A  | 09-22-1997                     | Kazuaki et al.                                     |   |                |
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| LV  | DA                    | ALIEV et al., "Development of Si(100) Surface Roughness at the Initial Stage of Etching in F2 and XeF2 Gases Ellipsometric Study", Surface Science 442 (1999), pp. 206-214.  |                |
|   | DB                    | GLIDEMEISTER, J.M., "Xenon Difluoride Etching System" (Nov. 17, 1997).   |                |
|   | DC                    | HABUKA et al., "Dominant Overall Chemical Reaction in a Chlorine Trifluoride-Silicon-Nitrogen System at Atmospheric Pressure", Japan Journal of Applied Physics Vol. 38 (1999), pp. 6466-6469.   |                |
|   | DD                    | HECHT et al., "A Novel X-ray Photoelectron Spectroscopy Study of the Al/SiO2 Interface", J. Appl. Phys. Vol. 57 (June 15, 1985), pp. 5256-5261.  |                |
|   | DE                    | HOULE, F.A., "Dynamics of SiF4 Desorption During Etching of Silicon by XeF2", IBM Almaden Research Center (April 15, 1987), pp. 1866-1872.   |                |
|   | DF                    | FLAMM et al., "XeF2 and F-Atom Reactions with Si: Their Significance for Plasma Etching", Solid State Technol. 28, 117 (1983).   |                |
|   | DG                    | IBBOTSON et al., "Plasmaless Dry Etching of Silicon with Fluorine-containing Compounds", J. Appl. Phys. Vol. 56 No. 10 (Nov. 1984), pp. 2939-2942.   |                |
|   | DH                    | IBBOTSON et al., "Comparison of XeF2 and F-atom Reactions with Si and SiO2", Applied Physics Letter, Vol. 44, 1129 (1984).   |                |
|   | DI                    | STRELLER et al., "Selectivity in Dry Etching of Si (100) and XeF2 and VUV Light", Elsevier Science B.V., Applied Surface Science Vol. 106 (1996), pp. 341-346.   |                |
|   | DJ                    |  |                |
| DK  |                       |  |                |

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|   |   |    | Filing Date              | 9/17/03                |         |
|   |   |    | First Named Inventor     | Shi                    |         |
|   |   |    | Group Art Unit           | 1765                   |         |
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| LV  | DL                    | WINTERS, H.F., "Etch Products from the Reaction of XeF <sub>2</sub> with SiO <sub>2</sub> , SiO <sub>3</sub> , Si <sub>3</sub> N <sub>4</sub> , SiC, and Si in the Presence of Ion Bombardment", J. Vac. Sci. Technol. B 1(4) (Oct/Dec 1983), pp. 927-931.     |                |
|   | DM                    | WINTERS et al., "The Etching of Silicon with XeF <sub>2</sub> Vapor", Appl. Phys. Letter, Vol. 34(1) (January 1, 1979), pp. 70-73.   |                |
|   | DN                    | XACTIX, Inc., Marketing Brochure (June 27, 1999).  |                |
|   | DO                    | "Xenon Difluoride Isotropic Etch System: Seeing is Believing", Surface Technology Systems Ltd. brochure, Newport, UK (date unknown).   |                |
|   | DP                    | Assorted promotional literature, Surface Technology Systems Ltd., Newport, UK (July 28, 1999).   |                |
| LV  |                       | Kurt Williams, Etch Rates for Micromachining Processing-Part II, 2003 IEEE, Pgs 761-778, Journal of Microelectromechanical Systems, Vol. 12, No. 6, December 2003.   |                |

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| C   | BA                    | ANDERSON, H.M., "Plasma Diagnostics for Semiconductor Processing", 2000 Digest of the LEOS Topical Meetings (July 24 - 28, 2000), pp. 117-118 (abstract only).   |                |
|   | BB                    | BARYSHEV et al., "Monitoring of $\text{SiO}_2/\text{Si}$ Plasma Etching and End-Point Detection", Mikroelektronika (Russia), Vol. 25, No. 5 (Sep/Oct 1996), pp. 373-379 (abstract only).   |                |
|   | BC                    | BASSOM et al., "Modeling and Optimizing $\text{XeF}_2$ -enhanced FIB Milling of Silicon", 25th International Symposium for Testing and Failure Analysis, Santa Clara, CA (Nov. 14 -18, 1999), pp. 255-261 (abstract only).   |                |
|   | BD                    | BERG et al., "Real-Time Control of Etching Processes: Experimental Results", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 3213 (1997), pp. 249-260 (abstract only).   |                |
|   | BE                    | CHAMBERS et al., "Endpoint Uniformity Sensing and Analysis in Silicon Dioxide Plasma Etching Using In Situ Mass Spectrometry", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 16, No. 6 (Nov/Dec 1998), pp. 2996-3002 (abstract only).                            |                |
|   | BF                    | CHAN et al., "Gas Phase Pulse Etching of Silicon for MEMS with Xenon Difluoride", Engineering Solutions for the Next Millenium: 1999 IEEE Canadian Conference on Electrical and Computer Engineering, Edmonton, Alberta, Vol. 3 (May 9 - 12, 1999), pp. 1637-1642 (abstract only). |                |
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|   | BH                    | CHEN et al., "Spatially Resolved Endpoint Detector for Plasma Etcher", 1997 IEEE International Symposium on Semiconductor Manufacturing Conference Proceedings, San Francisco, CA (Oct. 6 - 8, 1997), pp. B45 - B48 (abstract only).   |                |
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|   | BJ                    | HEINRICH et al., "Multichannel Process Monitor for Real-Time Film Thickness and Rate Measurements in Dry Etching and Deposition", Vacuum, Vol. 51, No. 4, (Dec. 1998), pp. 497-502 (abstract only).  |                |
| D   | BK                    | KOHLER et al., "Fabrication of Microlenses by Plasmaless Isotropic Etching Combined with Plastic Moulding", Sens. Actuators A, Phys. (Switzerland), Vol. A53, No. 1-3 (May 1996), pp. 361-363 (abstract only).   |                |

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| LV  | BL                    | LI et al., "Mass Spectrometric Measurements on Inductively Coupled Fluorocarbon Plasmas: Positive Ions, Radicals and Endpoint Detection", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 17, No. 5 (Sept. 1997), pp. 2438-2446 (abstract only).   |                |
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|   | BN                    | LITVAK, H.E., "End Point Control Via Optical Emission Spectroscopy", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 14, No. 1 (Jan/Feb 1996), pp. 516-520 (abstract only).  |                |
|   | BO                    | LU et al., "Effluent Monitoring with FTIR Spectroscopy for Low Open Area Oxide Etch Endpoint Detection", 8th International Symposium on Semiconductor Silicon, San Diego, CA, Vol. 2 (May 4 - 8, 1998), pp. 1250-1261 (abstract only).   |                |
|   | BP                    | MAYNARD et al., "Plasma Etching of Submicron Devices: In Situ Monitoring and Control by Multi-Wavelength Ellipsometry", Thin Solid Films (Switzerland), Vol. 313-314, No. 1-2 (Feb. 1998), pp. 398-405 (abstract only).  |                |
|   | BQ                    | MELVILLE et al., "Volatile Products and Endpoint Detection in Reactive Ion Etching of III-V Compounds with a Broad Beam ECR Source", Nuclear Instruments & Methods in Physics Research, Section B (Beam Interactions with Materials and Atoms), Vol. B106, No. 1-4 (Dec. 1995), pp. 179-182 (abstract only). |                |
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|   | BS                    | PERRIN, J., "Mass Spectrometry of Reactive Plasmas", Plasma Processing of Semiconductors, Chateau de Bonas, France (June 17 - 28, 1996), pp. 397-431 (abstract only).  |                |
|   | BT                    | RICHTER et al., "Exhaust Gas Monitoring: New Window Into Semiconductor Processing", Solid State Technol., Vol. 42, No. 5 (May 1999), pp. 61, 63-64, 68, 70-71 (abstract only).   |                |
|   | BU                    | SAITO et al., "Low Temperature Plasmaless Etching of Silicon Dioxide Film Using Chlorine Trifluoride Gas with Water Vapor", J. Electrochem. Soc., Vol. 147, No. 12 (Dec. 2000), pp. 4630-4632 (abstract only).   |                |
| LV  | BV                    | SEBEL et al., "Etching of Si Through a Thick Condensed XeF <sub>2</sub> Layer", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 5 (Sep/Oct 2000), pp. 2090-2097 (abstract only).   |                |

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| LV  | BW                    | SEBEL et al., "Reaction Layer Dynamics in Ion-Assisted Si/XeF <sub>2</sub> Etching: Temperature Dependence", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 6, (Nov. 2000), pp. 2759-2769 (abstract only).   |                |
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|   | BY                    | SUGANO et al., "Study on XeF <sub>2</sub> Pulse Etching Using Wagon Wheel Pattern", Proceedings of the 1999 International Symposium on Micromechanics and Human Science: Towards the New Century, Nagoya, Japan (Nov. 23 - 26, 1999), pp. 163-167 (abstract only).        |                |
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|   | CA                    | THOMAS et al., "Minimized Response Time of Optical Emission and Mass Spectrometric Signals for Optimized Endpoint Detection", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 14, No. 4 (July/Aug 1996), pp. 2531-2536 (abstract only).                   |                |
|   | CB                    | TODA et al., "Thin Beam Bulk Micromachining Based on RIE and Xenon Difluoride Silicon Etching", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 1 (June 16 - 19, 1997), pp. 671-674.                                      |                |
|   | CC                    | VUGTS et al., "Si/XeF <sub>2</sub> Etching: Reaction Layer Dynamics and Surface Roughening", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 14, No. 5 (Sept/Oct 1996), pp. 2780-2789 (abstract only).  |                |
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|   | CE                    | WAN et al., "Electron Cyclotron Resonance Plasma Reactor for SiO <sub>2</sub> Etching: Process Diagnostics, End-Point Detection, and Surface Characterization", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 13, No. 4 (July/Aug 1995), pp. 2035-2043 (abstract only). |                |
|   | CF                    | WANG et al., "Gas-Phase Silicon Etching with Bromine Trifluoride", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 2 (June 16 - 19, 1997), pp. 1505-1508 (abstract only).   |                |
| LV  | CG                    | WARD, P.P., "Plasma Process Control with Optical Emission Spectroscopy", 17th IEEE/CPMT International Electronics Manufacturing Technology Symposium: Manufacturing Technologies - Present and Future, Austin, TX (Oct. 2 - 4, 1995), pp. 166-169 (abstract only).        |                |

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| LV  | CH                    | WARNEKE, et al., "In Situ Characterization of CMOS Post-Process Micromachining", Sens. Actuators A, Phys. (Switzerland), Vol. A89, No. 1-2 (March 20, 2001), pp. 142-151 (abstract only).  |                |
|   | CI                    | WELCH et al., "Breaking the 0.5 Percent Exposed Area Etch Endpoint Barrier", Semicond. Int., Vol. 19, No. 8 (July 1996), pp. 269-270, 272, 274, 276 (abstract only).   |                |
|   | CJ                    | WODECKI, N.D., Low Open Area Multi-Layered Dielectric Film Etch Endpoint Detection Using EndPoint Plus (TM)", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 3882 (1999), pp. 231-238 (abstract only).                      |                |
|   | CK                    | WONG et al., "Endpoint Prediction for Polysilicon Plasma Etch Via Optical Emission Interferometry", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 15, No. 3, Pt. 2 (May/June 1997), pp. 1403-1408 (abstract only).   |                |
|   | CL                    | YUE et al., "Plasma Etching Endpoint Detection Using Multiple Wavelengths for Small Open Area Wafers", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 19, No. 1 (Jan. 2001), pp. 66-75 (abstract only).   |                |

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